

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Maruyama et al.
Appl. No.	:	10/522,036
Filed	:	January 19, 2005
For	:	CHEMICAL AMPLIFICATION TYPE POSITIVE PHOTORESIST COMPOSITION AND RESIST PATTERN FORMING METHOD
Examiner	:	Lee, Sin J
Group Art Unit	:	1752

AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **September 20, 2007**, please consider the following amendments and remarks.

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 10 of this paper.

Please
Enter
S.J.L.
11-23
2007